

ACKNOWLEDGEMENT RECEIPT

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Title of Invention

Methods for the optimization of substrate etching in a plasma processing system

Submission Type : Information Disclosure Statement

Application Number:

10/804430



EFS ID:

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First Named Applicant: Jisoo Kim

Attorney Docket Number: LMRX-P032/P1205

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File Listing:

Doc. Name	File Name	Size (Bytes)	Date Produced (yyyymmdd)
us-ids	LMRX-P032-usidst.xml	1001	2005-01-08
us-ids	us-ids.dtd	7763	2005-01-08
us-ids	us-ids.xsl	12026	2005-01-08
package-data	LMRX-P032-pkda.xml	1734	2005-01-08
package-data	package-data.dtd	27025	2005-01-08
package-data	us-package-data.xsl	19263	2005-01-08
Total files size		68812	

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